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Docket No.: 8733.378.00-US
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Myoung-Su Yang

Confirmation No.: 6030

Application No.: 09/748,871

Art Unit: 2812

Filed: December 28, 2000

Examiner: R. E. Pompey

For: METHOD OF FORMING A
POLYCRYSTALLINE SILICON LAYER

Customer No.: 30827

AMENDMENT AFTER FINAL ACTION (37 C.F.R. SECTION 1.116)

MS AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

INTRODUCTORY COMMENTS

In response to the Office Action dated April 22, 2004 (Paper No. 20040419), please amend the above-identified U.S. patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.